



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Inventors: Takashi SATO et al.	

Application No.: 10/781,652

) Group Art Unit: 2851

Filed: February 20, 2004

For: LITHOGRAPHY SIMULATION

METHOD, MASK PATTERN CORRECTION METHOD, AND SUBSTRATE TOPOGRAPHY CORRECTION METHOD

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

CLAIM FOR PRIORITY

Under the provisions of Section 119 of 35 U.S.C., applicants hereby claim the benefit of the filing date of Japanese Patent Application No. 2003-044443, for the above identified United States Patent Application.

In support of applicants claim for priority, filed herewith is one certified copy of the above.

Respectfully submitted,

FINNEGAN, HENDERSON, FARABOW, GARRETT & DUNNER, L.L.P.

Dated: July 12, 2004

Richard V. Burgujian

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